ERRATA

Erratum: “Energies, Charges, and Sizes of Clusters under Ion Sputtering of a Metal” [JETP 110, 722 (2010)]

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In the article, the reference to the paper by V.I. Matveev and S.A. Kochkin, *Vestnik PGU, Ser. Estestvennye i Tochnye Nauki*, no. 4, 69 (2008) is missing, in which an idealized problem of sputtering of a metal with an absolutely plane surface is considered and analogous results are obtained, while experiments on ion sputtering of a metal in the form of coupled polyatomic complexes (clusters) are usually carried out on targets with surfaces “pitted” by ion bombardment. In the article published in *JETP* **110**, 722 (2010), precisely the processes of ion sputtering with

targets complicated in this way are investigated; the extent of “pitting” of the surface is described quantitatively by introducing parameter h into formula (16). The values of $h = 1$ and 0 correspond, respectively, to a perfectly flat surface and for an extremely pitted surface, in which clusters with zero energy simply lie on the surface before sputtering. Thus, the results reported in *Vestnik PGU* no. 4, 69 (2008) are a special case of the general analysis carried out in *JETP* **110**, 722 (2010) for sputtering of the targets corresponding to real experimental investigations.